

Notice of References Cited	Application/Control No. 10/531,208	Applicant(s)/Patent Under Reexamination UEDA ET AL.	
	Examiner Sin J. Lee	Art Unit 1795	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Chemical Abstract 131:293 (an abstract for "Novel Dissolution Inhibitors Based on Calixarene Derivatives for Use in Chemical Amplification Resists", Polymeric Materials Science and Engineering (1999), Vol.81, pg.51-52).
	V	Tully et al ("Dendrimer-Based Chemically Amplified Resists for Sub-100 nm Lithography", Proceedings of SPIE, Vol.3999 (2000), pg.1202-1206).
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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